Chapter NR 264

ELECTRICAL AND ELECTRONIC COMPONENTS

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NR 264.01 Purpose. The purpose of this chapter is to establish effluent limitations, performance standards, and pretreatment standards for discharges of process wastes from the electrical and electronic components category of point sources and its subcategories.

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.02 Applicability. This chapter applies to any manufacturing operation which produces semiconductors, electronic crystals, cathode ray tubes, or luminescent materials and which discharges or may discharge process wastewater pollutants to waters of the state or into a publicly owned treatment works.

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.03 General definitions. The following definitions are applicable to the terms used in this chapter. Definitions of other terms and abbreviations are set forth in ss. NR 205.03, 205.04 and 211.03.

c1d XExisting sourceY means any point source, except a new source as defined in sub. c2d, from which pollutants may be discharged either into waters of the state or into a publicly owned treatment works.

c2d XNew sourceY means any point source from which pollutants are or may be discharged directly to waters of the state or into a publicly owned treatment works and for which construction commenced after August 24, 1982, for point sources subject to the semiconductor and electronic crystals subcategory or March 9, 1983, for point sources subject to the cathode ray tube and luminescent materials subcategories.

c3d XTTOY means total toxic organics. **History:** Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.04 Alternative to monitoring for total toxic organics. c1d Instead of monitoring for TTO, the certification set forth in sub. c3d may be used as a comment within the discharge monitoring report required by s. NR 205.07 c3d cdd or 211.15 c4d, if the following 4 conditions are met:

cad A direct discharger has submitted a solvent management

plan to the department; a source which discharges to a POTW has submitted a solvent management plan to the control authority;

cbd The department or control authority has approved the solvent management plan;

ccd The solvent management plan has been incorporated into the discharger[s permit; and

cdd The solvent management plan is being implemented to the satisfaction of the department or control authority.

c2d The solvent management plan shall specify the following:

cad The toxic organic compounds used;

cbd A toxic organic compound disposal method other than dumping, such as reclamation, contract hauling, or incineration.

ccd The procedures used to assure that toxic organic compounds do not routinely spill or leak into the wastewater.

c3d The following certification shall be used:

XBased on my inquiry of the person or persons directly responsible for managing compliance with the permit limitation for total toxic organics cTTOd, I certify that, to the best of my knowledge and belief, no dumping of concentrated toxic organics into the wastewaters has occurred since the filing of the last discharge monitoring report. I further certify that this facility is implementing the solvent management plan submitted to the department or POTW.Y

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.05 Compliance dates. c1d The following compliance dates apply to any source subject to this chapter which discharges to waters of the state:

cad Any existing source shall achieve the effluent limitations representing BPT by July 1, 1977.

cbd Except as provided in par. ccd, any existing source shall achieve the effluent limitations representing BAT and BCT by July 1, 1984.

ccd Existing sources subject to the semiconductor subcate-

gory or the electronic crystals subcategory shall achieve the BAT effluent limitation for fluoride by November 11, 1985.

cdd Any new source subject to this chapter shall achieve NSPS at the commencement of discharge.

c2d The following compliance dates apply to sources subject to this chapter which introduce process wastewater pollutants into a POTW:

cad Any existing source subject to the semiconductor subcategory shall achieve PSES by July 1, 1984.

cbd Any existing source subject to the electronic crystals subcategory shall achieve the PSES for TTO by July 1, 1984 and for arsenic by November 8, 1985.

ccd Any existing source subject to the cathode ray tube subcategory shall achieve the PSES by July 14, 1986.

cdd Any new source shall achieve PSNS at the commencement of discharge.

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

Subchapter I — Semiconductor Subcategory

NR 264.10 Applicability; description of the semiconductor subcategory. This subchapter applies to the discharge of pollutants to waters of the state and the introduction of pollutants into POTWs from all process operations, beginning with the use of crystal wafers, which lead to or are associated with the manufacture of semiconductors, except sputtering, vapor deposition, and electroplating.

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.11 Specialized definitions. The following definitions apply to the terms used in this subchapter:

c1d XSemiconductorY means a solid state electrical device which performs functions such as information processing and display, power handling, and interconversion between light energy and electrical energy.

c2d XTTOY means the sum of the concentrations of each of the following toxic organic compounds which is found in the discharge at a concentration greater than 10 micrograms per liter:

C	<i>U</i> 1
	naphthalene
	2 nitrophenol
	bis c2-ethylhexyld phthalate
	tetrachloroethylene
	toluene
	trichloroethylene
	2 chlorophenol
	2, 4 dichlorophenol
	1, 1 dichloroethylene
	2, 4, 6 trichlorophenol
	carbon tetrachloride
	1, 2 dichloroethane
	1, 1, 2 trichloroethane
	dichlorobromomethane

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.12 Effluent limitations representing the degree of effluent reduction attainable by the application of the best practicable control technology currently available. Except as provided in 40 CFR 125.30 to 125.32, any existing point source subject to this subchapter shall achieve the following effluent limitations representing the degree of effluent reduction attainable by application of BPT:

Table 1 Semiconductor

Semiconductor				
BPT Effluent Limitations				
Average of daily Maximum for values for 30 con- any 1 day secutive days				
Pollutant or pollutant property	milligra	nms per liter		
TTO	1.37			
pН	c1d	c1d		
1.1 11 11 11 11 11 11 11 11 11 11 11 11				

c1d Within the range of 6.0 to 9.0 at all times.

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.13 Effluent limitations representing the degree of effluent reduction attainable by the application of the best available technology economically achievable. Except as provided in 40 CFR 125.30 to 125.32, any existing point source subject to this subchapter shall achieve the following effluent limitations representing the degree of effluent reduction attainable by application of BAT:

Table 2 Semiconductor

Semiconductor				
BAT Effluent Limitations				
	Maximum for any 1 day	Average of daily values for 30 consecutive days		
Pollutant or pollutant property	milligra	ams per liter		
TTO	1.37			
Fluoride	32.0	17.4		

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.14 New source performance standards. Any new source subject to this subchapter shall achieve the following NSPS:

Table 3 Semiconductor

	Semileonaaetoi	
	NSPS	
		Average of daily
	Maximum for any	values for 30 con-
	1 day	secutive days
Pollutant or pollutant	milligrams per liter	
property		
TTO	1.37	
Fluoride	32.0	17.4
pН	c1d	c1d
1.1 11111111111111111111111111111111111	0.0 . 11 .	

c1d Within the range of 6.0 to 9.0 at all times.

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.15 Pretreatment standards for existing sources. Except as provided in ss. NR 211.13 and 211.14, any existing source subject to this subchapter which introduces pollutants into a POTW shall comply with ch. NR 211 and the TTO concentration in the discharge may not exceed 1.37 milligrams per liter for any one day.

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.17 Effluent limitations representing the degree of effluent reduction attainable by the application of the best conventional pollutant control technology. Except as provided in 40 CFR 125.30 to 125.32, any existing point source subject to this subchapter shall achieve a pH within the range of 6.0 to 9.0 at all times.

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

Subchapter II — Electronic Crystals Subcategory

NR 264.20 Applicability; description of the electronic crystals subcategory. This subchapter applies to the discharge of pollutants to waters of the state and the introduction of pollutants into POTWs resulting from the growing of crystals or the production of crystal wafers for use in the manufacture of electronic devices.

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.21 Specialized definitions. The following definitions apply to the terms used in this subchapter:

c1d XElectronic crystalsY means crystals or crystalline materials, such as crystals comprised of quartz, ceramic silicon, gallium arsenide, and indium arsenide, which, because of their unique structural and electrical properties, are used in electronic devices.

c2d XTTOY means the sum of the concentrations of each of the following toxic organic compounds which is found in the discharge at a concentration greater than 10 micrograms per liter:

1, 2, 4 trichlorobenzene	2, 4 dichlorophenol
chloroform	4 nitrophenol
1, 2 dichlorobenzene	pentachlorophenol
1, 3 dichlorobenzene	di-n-butyl phthalate
1, 4 dichlorobenzene	anthracene
ethylbenzene	1, 2 diphenylhydrazine
1, 1, 1 trichloroethane	isophorone
methylene chloride	butyl benzyl phthalate
naphthalene	1, 1 dichloroethylene
2 nitrophenol	2, 4, 6 trichlorophenol
bis c2-ethylhexyld phthalate	carbon tetrachloride
tetrachloroethylene	1, 2 dichloroethane
toluene	1,1,2 trichloroethane
trichloroethylene	dichlorobromomethane
2 chlorophenol	

NR 264.22 Effluent limitations representing the degree of effluent reduction attainable by the application

of the best practicable control technology currently

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

available. Except as provided in 40 CFR 125.30 to 125.32, any existing point source subject to this subchapter shall achieve the following effluent limitations representing the degree of effluent reduction attainable by application of BPT:

Table 4 Electronic Crystals

BPT Effluent Limitations			
	Maximum for any 1 day	Average of daily values for 30 consecutive days	
Pollutant or pollutant property	milligr	ams per liter	
TTO	1.37		
Arsenicc1d	2.09	0.83	
Fluoride	32.0	17.4	
TSS	61.0	23.0	
pН	c2d	c2d	

c1d The arsenic limitation only applies to manufacturers of gallium or indium arsenide crystals.

c2d Within the range of 6.0 to 9.0 at all times.

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.23 Effluent limitations representing the degree of effluent reduction attainable by the application of the best available technology economically achievable. Except as provided in 40 CFR 125.30 to 125.32, any existing point source subject to this subchapter shall achieve the following effluent limitations representing the degree of effluent reduction attainable by application of BAT:

Table 5
Electronic Crystals

BAT Effluent Limitations				
	Maximum for any 1 day	Average of daily values for 30 consecutive days		
Pollutant or pollutant property	milligra	ams per liter		
TTO	1.37			
Arsenicc1d	2.09	0.83		
Fluoride	32.0	17.4		

c1d The arsenic limitation only applies to manufacturers of gallium or indium arsenide crystals.

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.24 New source performance standards. Any new source subject to this subchapter shall achieve the standards set forth in s. NR 264.23.

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.25 Pretreatment standards for existing **sources.** Except as provided in ss. NR 211.13 and 211.14, any existing source subject to this subchapter which introduces pollutants into a POTW shall comply with ch. NR 211 and achieve the following PSES:

Table 6

Electronic Crystals				
PSES				
		Average of daily		
	Maximum for	values for 30 con-		
	any 1 day	secutive days		
Pollutant or pollutant	million	ams per liter		
property	mingi	anis per inter		
TTO	1.37	_		
Arsenicc1d	2.09	0.83		

c1d The arsenic limitation only applies to manufacturers of gallium or indium arsenide crystals.

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

264.26 Pretreatment standards for new sources. Except as provided in s. NR 211.13, any new source subject to this subchapter which introduces pollutants into a POTW shall comply with ch. NR 211 and comply with the standards set forth in s. NR 264.25.

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.27 Effluent limitations representing the degree of effluent reduction attainable by the application of the best conventional pollutant control technology. Except as provided in 40 CFR 125.30 to 125.32, any existing point source subject to this subchapter shall achieve the following effluent limitations representing the degree of effluent reduction attainable by application of BCT:

Table 7 Electronic Crystals

BCT Effluent Limitations			
	Maximum for any 1 day	Average of daily values for 30 consecutive days	
Pollutant or pollutant property	milligra	ams per liter	
TSS	61.0	23.0	
pH	c1d	c1d	

c1d Within the range of 6.0 to 9.0 at all times.

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

Subchapter III — Cathode Ray Tube Subcategory

NR 264.30 Applicability; description of the cathode ray tube subcategory. This subchapter applies to the discharge of pollutants to waters of the state and the introduction of pollutants into POTWs from the manufacture of cathode ray tubes. This subchapter does not apply to the manufacture of receiving or transmitting tubes.

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.31 Specialized definitions. The following definitions apply to the terms used in this subchapter:

c1d XCathode ray tubeY means an electronic device in which electrons focus through a vacuum to generate a controlled image on a luminescent surface.

c2d XTTOY means the sum of the concentrations of each of the following toxic organic compounds which is found in the discharge at a concentration greater than 10 micrograms per liter.

1, 1, 1 chloroform

trichloroethane

methylene chloride

bis c2-ethylhexyld phthalate

toluene

trichloroethylene

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.32 New source performance standards. Any new source subject to this subchapter shall achieve the following NSPS:

> Table 8 Cathode Ray Tube

Cathoue Ray Tube				
	NSPS			
	Maximum for			
	any 1 day	secutive days		
Pollutant or pollutant property	milligrams per	liter		
pН	c1d	cld		
TTO	1.58			
Cadmium	0.06	0.03		
Chromium	0.56	0.26		
Lead	0.72	0.27		
Zinc	0.80	0.33		
Fluoride	35.0	18.0		
TSS	46.0	24.0		

c1d Within the range of 6.0 to 9.0 at all times History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.33 Pretreatment standards for existing **sources.** Except as provided in ss. NR 211.13 and 211.14, any existing source subject to this subchapter which introduces pollutants into a POTW shall comply with ch. NR 211 and achieve the following PSES:

> Table 9 Cathode Ray Tube

	PSES	
		Average of daily
		values for 30 con-
D 11	any 1 day	secutive days
Pollutant or pollutant	milligr	ams per liter
property		ans per mer
TTO	1.58	
Cadmium	0.06	0.03
Chromium	0.65	0.30
Lead	1.12	0.41
Zinc	1.38	0.56
Fluoride	35.0	18.0

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.34 Pretreatment standards for new sources. Except as provided in s. NR 211.13, any new source subject to this subchapter which introduces pollutants into a POTW shall comply with ch. NR 211 and achieve the following PSNS:

Table 10 Cathode Ray Tube

Cat	node Ray Tube	
	PSNS	
	Maximum for any 1 day	Average of daily values for 30 consecutive days
Pollutant or pollutant property	milligrams per liter	
TTO	1.58	
Cadmium	0.06	0.03
Chromium	0.56	0.26
Lead	0.72	0.27
Zinc	0.80	0.33
Fluoride	35.0	18.0

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

Subchapter IV — Luminescent Materials Subcategory

NR 264.40 Applicability; description of the luminescent materials subcategory. This subchapter applies to the discharge of pollutants to waters of the state and the introduction of pollutants into POTWs resulting from the manufacture of materials, such as calcium halophosphate, yttrium oxide, zinc sulfide, and zinc-cadmium sulfide, which emit light upon excitation by energy sources such as photons, electrons, applied voltage, chemical reactions, or mechanical energy, and which are specifically used as coatings in fluorescent lamps and cathode ray tubes.

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.41 New source performance standards. Any new source subject to this subchapter shall achieve the following NSPS:

Table 11 Luminescent Materials

Euninescent Waterials		
	NSPS	
		Average of daily
	Maximum for	values for 30 con-
	any 1 day	secutive days
Pollutant or pollutant	milligrams per liter	
property		
pН	c1d	c1d
Cadmium	0.55	0.26
Antimony	0.10	0.04
Zinc	1.64	0.67
Fluoride	35.0	18.0
TSS	60.0	31.0

c1d Within the range of 6.0 to 9.0 at all times.

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

NR 264.42 Pretreatment standards for new sources. Except as provided in s. NR 211.13, any new source subject to this subchapter which introduces pollutants into a POTW shall comply with ch. NR 211 and achieve the following PSNS:

Table 12 Luminescent Materials

	PSNS	
		Average of daily
	Maximum for	values for 30 con-
	any 1 day	secutive days
Pollutant or pollutant	milligrams per liter	
property		
Cadmium	0.55	0.26
Antimony	0.10	0.04
Zinc	1.64	0.67
Fluoride	35.0	18.0
Zinc	1.64 35.0	0.67 18.0

History: Cr. Register, May, 1990, No. 413, eff. 6-1-90.

Note: The Wisconsin administrative code corresponds to the code of federal regulations as cross referenced in the following table:

State Code	Corresponding Federal Regulation
s. NR 205.03	40 CFR 401.11
s. NR 205.04	40 CFR 401.11
s. NR 205.07 c3d cdd	40 CFR 122.44 cid
ch. NR 211	40 CFR Part 403
s. NR 211.03	40 CFR 403.3
s. NR 211.13	40 CFR 403.7
s. NR 211.14	40 CFR 403.13
s. NR 211.15 c4d	40 CFR 403.12 ced
ch. NR 264	40 CFR Part 469